

# Bulk and Thin-Film Single Crystal Growth of

# Next-Generation Superhard, Electronic & Optical Materials

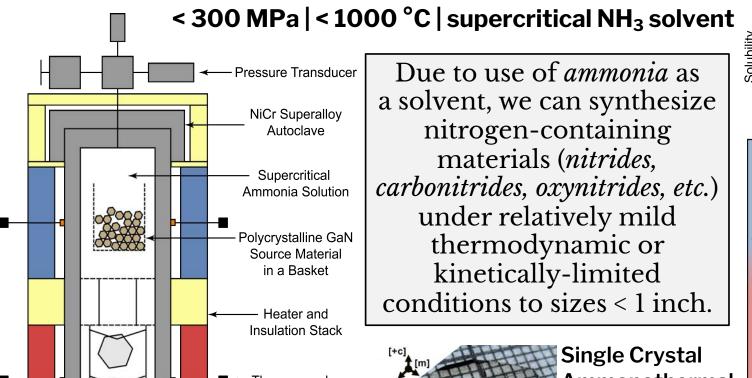
The MATS Group (PI: Siddha Pimputkar)

Materials Science & Engineering Department | Center for Photonics & Nanoelectronics



## **Solvothermal Methods**

#### Ammonothermal Method



# Thermocouples GaN Seed Crystals on a Stand Gallium Nitride $T_{melt} \approx 4000 \, ^{\circ}C$ $P_{melt} \approx 12 \, \text{GPa}$

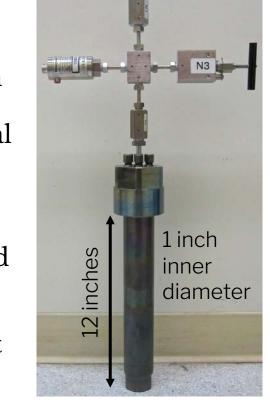
# MATS Facilities & Autoclaves

> 6 autoclaves in parallel | 2 independent setups | 1" inner diameter autoclaves



Our crystal growth facility is unique in the world due to our ability to pursue ammonothermal single crystal growth in novel, extremely corrosion resistant Mo-alloy, in traditional NiCr superalloy (right) or in SS autoclaves.

Operations require an oxygen-free environment and hence the use of hermetically sealed, inert atmosphere, 1-inch thick steel-walled containment vessels is mandated (left).



Source

Temperature

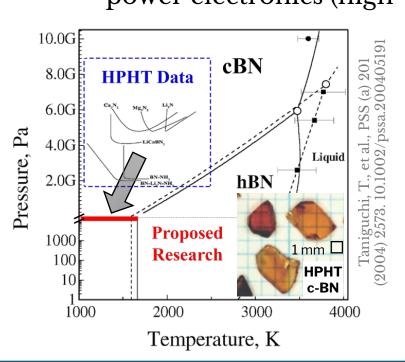
**→** ...

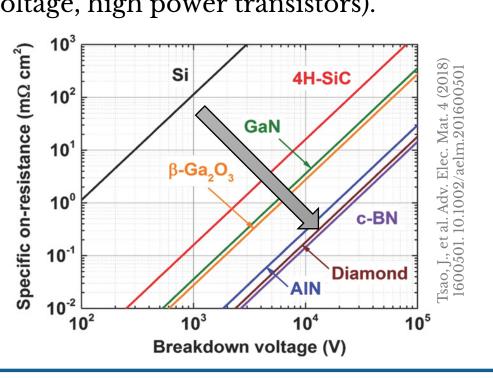
Transport

Seed

# Materials: e.g. cubic BN

'Low' temperature and pressure synthesis will result in > 1-inch boules suitable for use in mechanical systems (abrasives, heat sinking) and power electronics (high voltage, high power transistors).





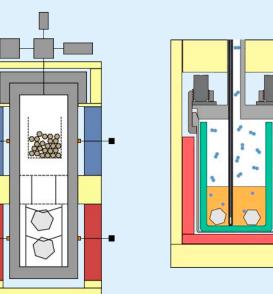
## Vision

As a group, we develop new growth systems to produce crystalline materials which are currently challenging to synthesize or scale in size. We are particularly interested in pursuing materials which have 'extreme' properties or are of particular value to enable highly efficient energy conversion (solar energy, electrical energy) or optoelectronic device of exceptional efficiency due to optimized pairing and tailoring of the substrate with the device layers.

We are vertically integrated, allowing us to develop next-gen devices on tailored substrates in innovative growth systems

#### Boule Growth

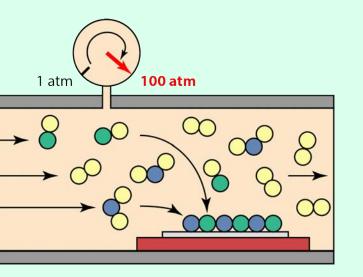
material properties | lattice constant
Grow large, single crystals for their
desired intrinsic properties or to
access novel substrates with
targeted lattice constants.



# Thin Films

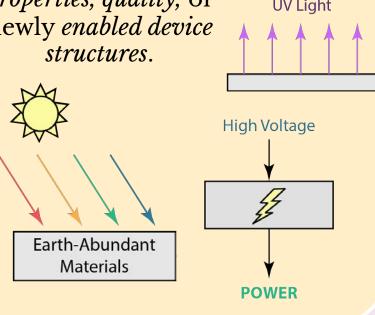
alloy compositions | doping | phases

Use *in-house* produced (or external) substrates to demonstrate *new* materials with *superior properties* as thin films using novel precursors.



#### Devices

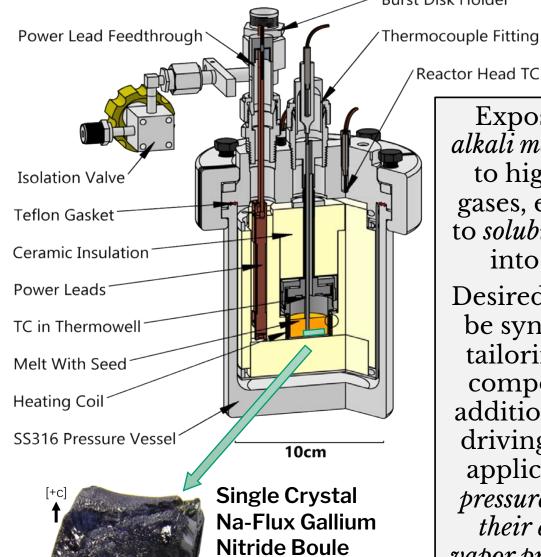
Demonstrate cuttingedge devices due to
superior material
properties, quality, or
newly enabled device
structures



## Flux Methods

## Alkali metal Fluxes

< 10 MPa | < 1200 °C | non-toxic | high nitrogen solubility



 $T_{flux} \approx 890 \, ^{\circ}C$ 

Exposing molten alkali metals (e.g. Na) to high pressure gases, e.g. N<sub>2</sub>, leads to solubility of, e.g. N, into the melt.

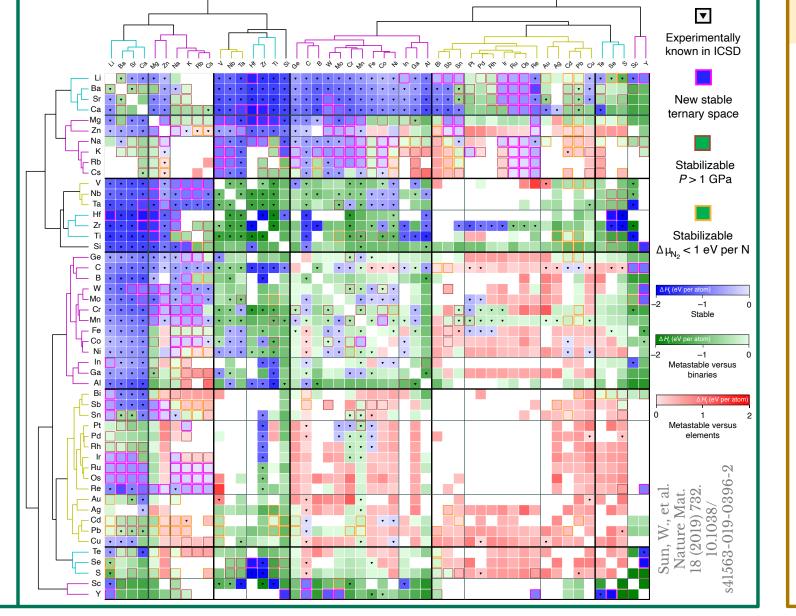
Desired crystals can be synthesized by tailoring the melt

be synthesized by tailoring the melt composition (e.g. addition of Ga) and driving growth via application of gas pressures in excess of their equilibrium vapor pressures or via temperature gradients.

Dollen, P., Pimputkar, S., et al. J. Cryst. Growth 456 (2016) 58. 10.1016/j.jcrysgro.2016.07.044; Dollen, P., Pimputkar, S., et al. J. Cryst. Growth 456 (2016) 67. 10.1016/j.jcrysgro.2016.08.018

# Materials: e.g. Ternary Nitrides

unexplored & new material systems | fundamental science 447 *stable* ternary nitrides predicted, only 213 demonstrated to-date. Requires *new approaches* to synthesize.



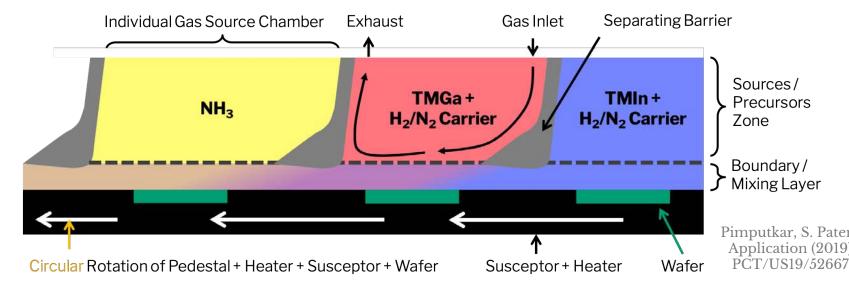
## **Chemical Vapor Deposition**

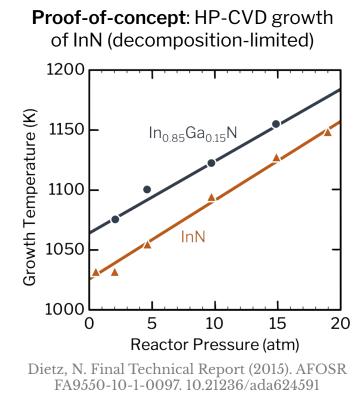


#### HPS-CVD

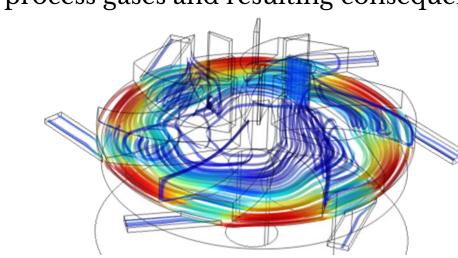
<100 atm | < 1300 °C | scalable design | grow decomposition-limited materials

A novel high pressure spatial chemical vapor deposition (HPS-CVD) tool is being developed to synthesize thin films of decomposition-limited materials by growing at pressures up to 100 atm, for the first time. Elevated pressures allow for higher growth temperatures (yielding high quality materials), increased alloy constituent compositions (via reduced decomposition), increased impurity concentrations (improved doping or desired element incorporation), and use of pressure-stabilized precursors.





Designs are being optimized using *CFD/thermal computational methods* (COMSOL/ANSYS) to demonstrate ability to *overcome known challenges* due to higher density of process gases and resulting consequences.



## Materials: e.g. Group III-N

UV-IR emitters | high frequency/power electronics | UWBG semiconductors High In-content III-N alloys can reveal the true potential of this semiconductor family via accessing the *entire solid solution region of AlInGaN*.

